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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/748,098	12/30/2003	Byung Chul Cho	YPL-0070	6908	
23413 7	590 08/18/2005		EXAM	EXAMINER	
CANTOR COLBURN, LLP 55 GRIFFIN ROAD SOUTH BLOOMFIELD, CT 06002			ZERVIGON, RUDY		
			ART UNIT	PAPER NUMBER	
			1763	1763	

DATE MAILED: 08/18/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)				
Office Action Commons	10/748,098	CHO ET AL.				
Office Action Summary	Examiner	Art Unit				
	Rudy Zervigon	1763				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply						
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailling date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	66(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) days ill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONEI	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 30 De	ecember 2003.					
	action is non-final.					
· <u></u>						
closed in accordance with the practice under E	•					
Disposition of Claims						
4) ☐ Claim(s) 1-7 is/are pending in the application. 4a) Of the above claim(s) is/are withdraw 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-7 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or						
Application Papers						
9)☐ The specification is objected to by the Examiner. 10)☒ The drawing(s) filed on <u>30 December 2003</u> is/are: a)☐ accepted or b)☒ objected to by the Examiner.						
Applicant may not request that any objection to the	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).					
	Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.					
Priority under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 						
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P					
Paper No(s)/Mail Date	6) Other:					

DETAILED ACTION

Drawings

1. The drawings are objected to under 37 CF R 1.83(a). The drawings must show every feature of the invention specified in the claims. Therefore, the "exhaust unit", "diffusion region", "convex portions" and "concave portions" must be shown or the feature canceled from the claims. No new matter should be entered.

Corrected drawing sheets in compliance with 37 CFR 1.121(d) are required in reply to the Office action to avoid abandonment of the application. Any amended replacement drawing sheet should include all of the figures appearing on the immediate prior version of the sheet, even if only one figure is being amended. The figure or figure number of an amended drawing should not be labeled as "amended." If a drawing figure is to be canceled, the appropriate figure must be removed from the replacement sheet, and where necessary, the remaining figures must be renumbered and appropriate changes made to the brief description of the several views of the drawings for consistency. Additional replacement sheets may be necessary to show the renumbering of the remaining figures. Each drawing sheet submitted after the filing date of an application must be labeled in the top margin as either "Replacement Sheet" or "New Sheet" pursuant to 37 CFR 1.121(d). If the changes are not accepted by the examiner, the applicant will be notified and informed of any required corrective action in the next Office action. The objection to the drawings will not be held in abeyance.

2. The drawings are objected to under 37 CFR 1.83(a). The drawings must show every feature of the invention specified in the claims. Therefore, the "first main flow paths which are

formed on the bottom of the connecting unit" must be shown or the feature canceled from the claims. No new matter should be entered. Could 70, Figure 5, really be 71, of Figure 2?

Corrected drawing sheets in compliance with 37 CFR 1.121(d) are required in reply to the Office action to avoid abandonment of the application. Any amended replacement drawing sheet should include all of the figures appearing on the immediate prior version of the sheet, even if only one figure is being amended. The figure or figure number of an amended drawing should not be labeled as "amended." If a drawing figure is to be canceled, the appropriate figure must be removed from the replacement sheet, and where necessary, the remaining figures must be renumbered and appropriate changes made to the brief description of the several views of the drawings for consistency. Additional replacement sheets may be necessary to show the renumbering of the remaining figures. Each drawing sheet submitted after the filing date of an application must be labeled in the top margin as either "Replacement Sheet" or "New Sheet" pursuant to 37 CFR 1.121(d). If the changes are not accepted by the examiner, the applicant will be notified and informed of any required corrective action in the next Office action. The objection to the drawings will not be held in abeyance.

Claim Rejections - 35 USC § 112

3. The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

4. Claim 3 is rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the enablement requirement. The claim contains subject matter which was not described in the specification in such a way as to enable one skilled in the art to which it pertains, or with which

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it is most nearly connected, to make and/or use the invention. Applicant's claim 3 requires "a diffusion region having a plurality of convex portions and a plurality of concave portions is formed on the top surface of the lower diffusion block (37, Figures 6, 8D; column 6, lines 38-65)", and "the convex portions and the second spray holes are formed in the concave portions". The specification, describing the drawings, provides no teaching as to where "a diffusion region" on the "lower diffusion block (37, Figures 6, 8D; column 6, lines 38-65)" is for the reader to locate Applicant's "convex portions" and Applicant's "concave portions".

Claim Rejections - 35 USC § 103

- 5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 6. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).
- 7. Claims 1-3, and 5-7 are rejected under 35 U.S.C. 103(a) as being unpatentable over Park et al (WO 03/009352 A1) in view of Murakami; Takeshi et al. (US 5,728,223 A). Park teaches:

i. A reaction chamber (100; Figure 3) for depositing a thin film (page 8, lines 11-19), the reaction chamber (100; Figure 3) comprising: a reactor block (110; Figure 3; page 8, lines 11-19); a wafer block (120; Figure 3; page 8, lines 11-19) located inside the reactor block (110; Figure 3; page 8, lines 11-19); a top plate (130; Figure 3; page 8, lines 20-26) which covers the reactor block (110; Figure 3; page 8, lines 11-19) to maintain a predetermined pressure; a feeding unit (piece above immediately 130, 122, 122a, 121, 121a; not labeled Figure 3) which supplies a first reactive gas (122; Figure 3; page 8, lines 20-26) and a second reactive gas (121; Figure 3; page 8, lines 20-26); a shower head (140; Figure 3, 12; page 8, lines 20-26), which is installed in the top plate (130; Figure 3; page 8, lines 20-26) and includes a plurality of first spray holes (141c; Figure 12; page 11, lines 13-25) for spraying the first reactive gas (122; Figure 3; page 8, lines 20-26) supplied from the feeding unit (piece above immediately 130, 122, 122a, 121, 121a; not labeled Figure 3) on a wafer and a plurality of second spray holes (142c; Figure 12; page 11, lines 13-25) for spraying the second reactive gas (121; Figure 3; page 8, lines 20-26) supplied from the feeding unit (piece above immediately 130, 122, 122a, 121, 121a; not labeled Figure 3); and an exhaust unit ("exhaust unit"; not shown; page 8, line 17) which expels gases (121, 122; Figure 3; page 8, lines 20-26) from the reactor block (110; Figure 3; page 8, lines 11-19), the feeding unit (piece above immediately 130, 122, 122a, 121, 121a; not labeled Figure 3) comprising: a feeding block (piece above immediately 130; not labeled Figure 3) that is connected to the shower head (140; Figure 3,12; page 8, lines 20-26); a distributing block (122; Figure 3) which is connected to a first gas (line upstream of 122; Figure 3; page 8, lines 20-26) supply line to uniformly distribute the

first reactive gas (122; Figure 3; page 8, lines 20-26); two or more first gas (line upstream of 122; Figure 3; page 8, lines 20-26) transfer pipes (122a; Figure 3; page 8, lines 20-26) which connect the feeding block (piece above immediately 130; not labeled Figure 3) to the distributing block (122; Figure 3); and a second gas (121; Figure 3; page 8, lines 20-26) transfer pipe (121a; Figure 3; page 8, lines 20-26) which is formed in the center of the feeding block (piece above immediately 130; not labeled Figure 3) and connected to the second gas (121; Figure 3; page 8, lines 20-26) supply line (piping upstream of 121), the shower head (140; Figure 3,12; page 8, lines 20-26) comprising an upper diffusion block (140; Figure 3,12; page 8, lines 20-26) connected to the bottom of the feeding unit (piece above immediately 130, 122, 122a, 121, 121a; not labeled Figure 3) – claim 1

ii. Park's upper diffusion block (140; Figure 3,12; page 8, lines 20-26) comprising: a connecting unit (outer ring part containing 142; Figure 3,12; page 8, lines 20-26) which is connected to Park's feeding block (piece above immediately 130; not labeled Figure 3) and includes first feeding holes (142; Figure 3,12; page 8, lines 20-26) which are respectively connected to Park's first gas (line upstream of 122; Figure 3; page 8, lines 20-26) transfer pipes (122a; Figure 3; page 8, lines 20-26) and a second feeding hole (141; Figure 3,12; page 8, lines 20-26) which is connected to Park's second gas (121; Figure 3; page 8, lines 20-26) transfer pipe (121a; Figure 3; page 8, lines 20-26); a plurality of first main flow paths (142a; Figure 12; page 8, lines 20-26) which are formed on Park's bottom of Park's connecting unit (outer ring part containing 142; Figure 3,12; page 8, lines 20-26), which are connected to Park's first feeding holes (142; Figure 3,12; page 8, lines 20-26), respectively, and are radially and symmetrically formed around

Park's center of Park's connecting unit (outer ring part containing 142; Figure 3,12; page 8, lines 20-26); and a plurality of first sub-flow paths (142b; Figure 12; page 8, lines 20-26), which are formed in Park's bottom of Park's connecting unit (outer ring part containing 142; Figure 3,12; page 8, lines 20-26) and extend perpendicularly from each of Park's first main flow paths (142a; Figure 12; page 8, lines 20-26) – claim 1

- iii. Park's reaction chamber (100; Figure 3) of claim 1, wherein Park's first gas (line upstream of 122; Figure 3; page 8, lines 20-26) transfer pipes (122a; Figure 3; page 8, lines 20-26) are symmetrically disposed between Park's feeding block (piece above immediately 130; not labeled Figure 3) and Park's distributing block (122; Figure 3), as claimed by claim 2
- iv. Park's reaction chamber (100; Figure 3) of claim 1, wherein Park's upper diffusion block, Park's intermediate diffusion block, and Park's lower diffusion block (37, Figures 6, 8D; column 6, lines 38-65) are integrally formed (140; Figure 3,12; page 8, lines 20-26), as claimed by claim 7

Park does not teach:

i. an intermediate diffusion block adhered to Park's bottom of Park's upper diffusion block (140; Figure 3,12; page 8, lines 20-26), and a lower diffusion block (37, Figures 6, 8D; column 6, lines 38-65) adhered to the bottom of the intermediate diffusion block, the intermediate diffusion block comprising: a plurality of second main flow paths, which are formed on the intermediate diffusion block and respectively correspond to Park's first main flow paths (142a; Figure 12; page 8, lines 20-26); a plurality of second sub-flow paths which are formed on the intermediate diffusion block and respectively correspond

to Park's first sub-flow paths (142b, Figure 12; page 8, lines 20-26); a plurality of first distributing holes which are formed at regular intervals in the second sub-flow paths and second main flow paths, and a second distributing hole connected to Park's second feeding hole (141; Figure 3,12; page 8, lines 20-26), a lower diffusion block (37, Figures 6, 8D; column 6, lines 38-65) comprising: a plurality of first spray holes connected to the first distributing holes, respectively, for spraying Park's first reactive gas (122; Figure 3; page 8, lines 20-26) on Park's wafer; and a plurality of second spray holes formed between Park's first spray holes for spraying Park's second reactive gas (121; Figure 3; page 8, lines 20-26) on Park's wafer – claim 1

- ii. Park's reaction chamber of claim 1, wherein a diffusion region having a plurality of convex portions and a plurality of concave portions is formed on the top surface of the lower diffusion block, and the first spray holes are formed in the convex portions and thr second spray holes are formed in the concave portions, as claimed by claim 3
- paths of Park's upper diffusion block (140; Figure 3,12; page 8, lines 20-26) has the same shape as each of the second sub-flow paths of the intermediate diffusion block, and each of the first main flow paths of Park's upper diffusion block (140; Figure 3,12; page 8, lines 20-26) has the same shape as each of the second main flow paths of the intermediate diffusion block, as claimed by claim 5
- iv. Park's reaction chamber (100; Figure 3) of claim 1, wherein the number of Murakami's first feeding holes (142; Figure 3,12; page 8, lines 20-26) is proportional to each of the

number of the first main flow paths and the number of the second main flow paths, as claimed by claim 6

Murakami teaches a wafer processing apparatus (Figure 1) and process gas distribution plates (31-33 Figures 6, 8a-c; column 6; lines 38-65) including:

i. an intermediate diffusion block (32, Figures 6, 8B; column 6, lines 38-65) adhered to Murakami's bottom of Murakami's upper diffusion block (31, Figures 6, 8A; column 6, lines 38-65), and a lower diffusion block (37, Figures 6, 8D; column 6, lines 38-65) adhered to the bottom of the intermediate diffusion block (32, Figures 6, 8B; column 6, lines 38-65), the intermediate diffusion block (32, Figures 6, 8B; column 6, lines 38-65) comprising: a plurality of second main flow paths (main branch on 32, Figures 6, 8C; column 6, lines 38-65), which are formed on the intermediate diffusion block (32, Figures 6, 8B; column 6, lines 38-65) and respectively correspond to Murakami's first main flow paths (main branch on 31, Figures 6, 8A; column 6, lines 38-65); a plurality of second sub-flow paths (perpedicular branch to main branch on 32, Figures 6, 8A; column 6, lines 38-65) which are formed on the intermediate diffusion block (32, Figures 6, 8B; column 6, lines 38-65) and respectively correspond to Murakami's first sub-flow paths (perpedicular branch to main branch on 31, Figures 6, 8A; column 6, lines 38-65); a plurality of first distributing holes (holes in 33, Figures 6, 8C; column 6, lines 38-65) which are formed at regular intervals in the second sub-flow paths (perpedicular branch to main branch on 32, Figures 6, 8A; column 6, lines 38-65) and second main flow paths (main branch on 32, Figures 6, 8C; column 6, lines 38-65); and a second distributing hole (24a, Figures 8A; column 6, lines 38-65) connected to Murakami's second feeding hole (24b, Figures 8B; column 6, lines 38-65), a lower diffusion block (37, Figures 6, 8D; column 6, lines 38-65) comprising: a plurality of first spray holes (42, Figure 6; column 6, lines 38-65) connected to the first distributing holes (holes in 33, Figures 6, 8C; column 6, lines 38-65), respectively, for spraying Murakami's first reactive gas on Murakami's wafer; and a plurality of second spray holes (43,44, Figure 6; column 6, lines 38-65) formed between Murakami's first spray holes (42, Figure 6; column 6, lines 38-65) for spraying Murakami's second reactive gas on Murakami's wafer – claim 1

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- ii. Murakami's reaction chamber (100; Figure 3) of claim 1, wherein a diffusion region (37; Figure 6) having a plurality of convex portions (pieces between 44; Figure 6) and a plurality of concave portions (44; Figure 6) is formed on Murakami's top surface of Murakami's lower diffusion block (37, Figures 6, 8D; column 6, lines 38-65), and Murakami's first spray holes (42, Figure 6; column 6, lines 38-65) are formed in Murakami's convex portions (pieces between 44; Figure 6) and Murakami's second spray holes (43,44, Figure 6; column 6, lines 38-65) are formed in Murakami's concave portions (44; Figure 6), as claimed by claim 3
- iii. Murakami's reaction chamber (100; Figure 3) of claim 1, wherein each of Murakami's first sub-flow paths (perpedicular branch to main branch on 31, Figures 6, 8A; column 6, lines 38-65) of Murakami's upper diffusion block (31, Figures 6, 8A; column 6, lines 38-65) has Murakami's same shape as each of the second sub-flow paths (perpedicular branch to main branch on 32, Figures 6, 8A; column 6, lines 38-65) of Murakami's intermediate diffusion block (32, Figures 6, 8B; column 6, lines 38-65), and each of Murakami's first main flow paths (main branch on 31, Figures 6, 8A; column 6, lines 38-65).

65) of Murakami's upper diffusion block (31, Figures 6, 8A; column 6, lines 38-65) has Murakami's same shape as each of the second main flow paths (main branch on 32, Figures 6, 8C; column 6, lines 38-65) of the intermediate diffusion block (32, Figures 6, 8B; column 6, lines 38-65), as claimed by claim 5

iv. Murakami's reaction chamber (100; Figure 3) of claim 1, wherein Murakami's number of Murakami's first feeding holes (35; Figure 6) is proportional to each of Murakami's number of Murakami's first main flow paths (main branch on 31, Figures 6, 8A; column 6, lines 38-65) and Murakami's number of Murakami's second main flow paths (main branch on 32, Figures 6, 8C; column 6, lines 38-65), as claimed by claim 6

It would have been obvious to one of ordinary skill in the art at the time the invention was made to replace Park's gas distribution components (Figure 6) with Murakami's gas distribution components (Figure 6).

Motivation to replace Park's gas distribution components (Figure 6) with Murakami's gas distribution components (Figure 6) is for providing for a uniform flow of process gasses over a wide area of substrates resulting in uniform films over wide areas of substrates as taught by Murakami (column 8; lines 18-46).

8. Claim 4 is rejected under 35 U.S.C. 103(a) as being unpatentable over Park et al (WO 03/009352 A1) and Murakami; Takeshi et al. (US 5,728,223 A) in view of Hayakawa; Yukihiro et al. (US 5,447,568 A). Park and Murakami are discussed above. Park and Murakami do not teach Murakami's reaction chamber (100; Figure 3) of claim 1, wherein a temperature sensor and a heater are mounted on Murakami's feeding block (piece above immediately 130; not labeled

Figure 3) to control Murakami's temperature of Murakami's reactive gases (121, 122; Figure 3; page 8, lines 20-26), as claimed by claim 4.

Hayakawa teaches a wafer processing apparatus (Figure 10) including a gas distribution plate (3306; Figure 10,11) with a heater (3307; Figure 11) controlled by temperature sensors (4001; Figure 11).

It would have been obvious to one of ordinary skill in the art at the time the invention was made to add Hayakawa's heated and controlled (4000) gas distribution plate (3306; Figure 10,11) to the apparatus of Park and Murakami.

Motivation to add Hayakawa's heated and controlled gas distribution plate (3306; Figure 10,11) to the apparatus of Park and Murakami is for controlling the feed rate of gas as taught by Hayakawa (column 13; lines 43-48).

Conclusion

9. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. WO 2004049413 A1; US 20040191413 A1.

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10. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Rudy Zervigon whose telephone number is (571) 272.1442. The examiner can normally be reached on a Monday through Thursday schedule from 8am through 7pm. The official fax phone number for the 1763 art unit is (703) 872-9306. Any Inquiry of a general nature or relating to the status of this application or proceeding should be directed to the Chemical and Materials Engineering art unit receptionist at (571) 272-1700. If the examiner can not be reached please contact the examiner's supervisor, Parviz Hassanzadeh, at

(571) 272-1435.